

include a plurality of widthwise metallic lines, lengthwise metallic lines and connections constituted by crosses of the widthwise metallic lines and the lengthwise metallic lines. In step 304, a plurality of conductive pads are formed, wherein the conductive pads are arranged in array manner and are electrically connected to the net-shaped metallic lines.

[0038] Referring to FIGS. 8 and 9 again, the method for manufacturing a TFT substrate in this embodiment of the present invention further includes the following step of: forming a plurality of scan lines 162 and data lines 164 on the transparent substrate 120, wherein the widthwise metallic lines 152 and the scan lines 162 are simultaneously formed by the same photolithography & etching processes, and the lengthwise metallic lines 154 and the data lines 164 are simultaneously formed by the same photolithography & etching processes.

[0039] Referring to FIG. 10 again, a method for manufacturing a TFT substrate in another embodiment of the present invention further includes the following step of: forming a plurality of scan lines 162 and data lines 164 on the transparent substrate 120, wherein formation steps of the widthwise metallic lines 152 and the lengthwise metallic lines 154 are earlier than a formation step of the scan lines 162.

[0040] Referring to FIG. 11, a method for manufacturing a TFT substrate in a further embodiment of the present invention further includes the following step of: forming a plurality of pixel electrode 166 on the transparent substrate 120, wherein the widthwise and lengthwise metallic lines 152, 154 and the pixel electrodes 166 are simultaneously formed by the same photolithography & etching processes.

[0041] Referring to FIG. 15, it depicts a method for manufacturing a CF substrate according to an embodiment of the present invention. In step 400, a transparent substrate. In step 402, a plurality of black matrixes are formed on the transparent substrate. In step 404, a plurality of color filters are formed on the transparent substrate and the black matrixes, wherein the color filter located on the black is formed to a protrusion. In step 406, by the same formation step, a plurality of spacers are formed on the protrusions of the color filters, and a plurality of protrudent portions are simultaneously formed on the black matrixes. In step 408, a transparent electrode is formed for covering the transparent substrate, the black matrixes, the color filters, the spacer and the protrudent portions.

[0042] Although the invention has been explained in relation to its preferred embodiment, it is not used to limit the invention. It is to be understood that any other possible modifications and variations can be made by those skilled in the art without departing from the spirit and scope of the invention as hereinafter claimed.

What is claimed is:

1. An in-cell touch-sensitive panel comprising:
 - a thin film transistor (TFT) substrate comprising:
 - a net-shaped readout circuit comprising a plurality of widthwise and lengthwise readout lines, wherein the widthwise readout lines are electrically connected to the lengthwise readout lines; and
 - a plurality of conductive pads arranged in array manner and electrically connected to the net-shaped readout circuit; and
 - a color filter (CF) substrate opposite to the TFT substrate and comprising:
 - a plurality of spacers adapted to keep a first gap between the TFT and CF substrates:

- a plurality of protrudent portions corresponding to the conductive pads, wherein there is a second gap between the protrudent portion and the conductive pad; and
 - a transparent electrode adapted to cover the spacers and the protrudent portion.
- 2. The in-cell touch-sensitive panel as claimed in claim 1, wherein the net-shaped readout circuit further comprises a plurality of connections constituted by crosses of the widthwise and lengthwise readout lines, and the conductive pads are adjacent to the connections respectively.
- 3. The in-cell touch-sensitive panel as claimed in claim 1, further comprising:
 - a plurality of scan lines and data lines, wherein the widthwise readout lines are parallel to the scan lines, and the lengthwise readout lines are parallel to the data lines.
- 4. The in-cell touch-sensitive panel as claimed in claim 3, wherein the widthwise readout lines and the scan lines are located the same level, and the lengthwise readout lines and the data lines are located the same level.
- 5. The in-cell touch-sensitive panel as claimed in claim 4, further comprising:
 - a plurality of plated through holes adapted to electrically connected the conductive pads to the net-shaped readout circuit.
- 6. The in-cell touch-sensitive panel as claimed in claim 5, further comprising:
 - a plurality of metallic extension layers adapted to be electrically connected to the plated through holes.
- 7. The in-cell touch-sensitive panel as claimed in claim 6, wherein the metallic extension layers are made of transparent metal.
- 8. The in-cell touch-sensitive panel as claimed in claim 3, further comprising:
 - a first transparent substrate, wherein the widthwise and lengthwise readout lines are located between the scan lines and the first transparent substrate.
- 9. The in-cell touch-sensitive panel as claimed in claim 8, further comprising:
 - a plurality of plated through holes adapted to electrically connected the conductive pads to the net-shaped readout circuit.
- 10. The in-cell touch-sensitive panel as claimed in claim 1, further comprising:
 - a plurality of pixel electrodes, wherein the widthwise readout lines and the lengthwise readout lines are located on the same level.
- 11. The in-cell touch-sensitive panel as claimed in claim 10, wherein the conductive pads are directly electrically connected to the net-shaped readout circuit.
- 12. The in-cell touch-sensitive panel as claimed in claim 11, wherein conductive pads are directly disposed at connections between the widthwise readout lines and the lengthwise readout lines.
- 13. The in-cell touch-sensitive panel as claimed in claim 2, wherein the net-shaped readout circuit is net-shaped readout metallic lines, and the widthwise readout line and the lengthwise readout line are metallic lines.
- 14. The in-cell touch-sensitive panel as claimed in claim 1, wherein the CF substrate further comprises:
 - a second transparent substrate;
 - a plurality of black matrixes disposed on the second transparent substrate; and